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Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Art Unit 2851

Re: U.S. Utility Patent Application
Application No. 10/632,798; Filed: August 4, 2003
For: **System and Method to Increase Throughput in a Dual Substrate
Stage Double Exposure Lithography System**

Inventors: Galburst *et al.*
Our Ref: 1857.1710001

Sir:

Transmitted herewith for appropriate action are the following documents:

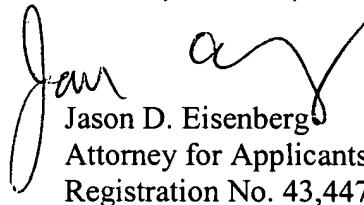
1. Reply to Restriction Requirement; and
2. One (1) return postcard.

It is respectfully requested that the attached postcard be stamped with the date of filing of these documents, and that it be returned to our courier. In the event that extensions of time are necessary to prevent abandonment of this patent application, then such extensions of time are hereby petitioned.

The U.S. Patent and Trademark Office is hereby authorized to charge any fee deficiency, or credit any overpayment, to our Deposit Account No. 19-0036.

Respectfully submitted,

STERNE, KESSLER, GOLDSTEIN & FOX P.L.L.C.


Jason D. Eisenberg
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JDE/kim
Enclosures

243411.1



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Galburt *et al.*

Appl. No.: 10/632,798

Filed: August 4, 2003

For: **System and Method to Increase
Throughput in a Dual Substrate
Stage Double Exposure
Lithography System**

Confirmation No.: 7458

Art Unit: 2851

Examiner: H. Nguyen

Atty. Docket: 1857.1710001

Reply to Restriction Requirement

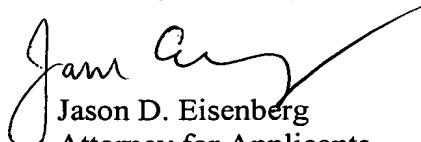
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the Office Action dated March 9, 2004, requesting an election of one invention to prosecute in the above-referenced patent application, Applicants hereby provisionally elect to prosecute the invention of Group I, represented by claims 1, 3 and 4. It is not believed that extensions of time are required, beyond those that may otherwise be provided for in accompanying documents. However, if additional extensions of time are necessary to prevent abandonment of this application, then such extensions of time are hereby petitioned under 37 C.F.R. § 1.136(a), and any fees required therefor are hereby authorized to be charged to our Deposit Account No. 19-0036.

Respectfully submitted,

STERNE, KESSLER, GOLDSTEIN & FOX P.L.L.C.


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Date: 3/22/04

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